



אוניברסיטת בן-גוריון בנגב  
Ben-Gurion University  
of the Negev

Nano-Fabrication  
Center

# CVD / LPCVD

## Expertech



## Description

Two high temperature compact reactors CTR 125 provide both atmospheric pressure (CVD) and Low vacuum (LPCVD) chemical vapor deposition processes.

The CVD system is used for silicon oxide ( $\text{SiO}_2$ ) films on silicon wafer by means of its diffusion.

The LPCVD system is used for deposit of amorphous- or poly- silicon on substrates.

## Specifications / Capabilities

Production style performance in a small footprint;

Fully automated, recipe driven processing.

LPCVD & CVD up to 4" wafer size and 25 wafers in one cycle

### Applications

Thermal Oxide or Silicon Dioxide ( $\text{SiO}_2$ ) is the insulating layer commonly used in semiconductors.

Amorphous silicon (a-Si) is the non-crystalline form of Si used for solar cells and thin film transistors in LCD displays.

Solar cells, MEMS etc...

## Materials

## Link

<http://www.exper-tech.com/>

<http://www.exper-tech.com/products/compact-thermal-reactor/>